ABSTRACT

MASK BLANK AND METHOD OF MANUFACTURING MASK BLANK

A mask blank of the invention includes: a transparent substrate having a surface; and a mask layer stacked on the surface of the transparent substrate. The mask layer contains nitrogen, carbon, oxygen, and chromium. The mask layer has an uppermost surface on the opposite side of the surface of the transparent substrate. An oxygen content rate of the uppermost surface of the mask layer is in a range of 65 to 72atm%. (fig.1)